

# UVtransfer

## Production Systems for microLED Mass Transfer

The UVtransfer system for microLED LIFT.

The systems from the UVtransfer product family are the solution to push microLED display manufacturing to an industrial level.



### FEATURES

- Fully automated system with fab integration to provide a complete solution to the customer
- High resolution optics combined with precision mechanics to transfer smallest LEDs down to  $5 \times 5 \mu\text{m}^2$
- $28 \times 1 \text{ mm}^2$  field size, 300 Hz rep rate and 300mm/s stage speed for highest throughput
- Double receiver stage for high system for outstanding system efficiency
- Triple donor stage for RGB generation in one process step and to minimize loading times and to optimize the die-to-die placing accuracy or single tripod donor stage to compensate wafer bow
- Outstanding SW features like digital twin and path planning for process simulation and optimization

### APPLICATIONS

- MicroLED mass transfer (pitch conversion and RGB pixel generation) in the display production
  - From an EpiWafer to a temporary carrier or backplane
  - From a carrier to a second carrier or backplane

Specifications		UVtransfer
LIFT and Repair System		Fully automated system for 24/7 usage in an industrial environment
Dimensions (W x L x H)		Approx. 3000 x 8000 x 3300 mm <sup>3</sup>
Laser and Optics		
Laser		Coherent deep UV laser 248 nm LIFT System: LEAP 300K
Optical System		Mask Imaging system for high homogeneity, stability and flexibility
Field Size		LIFT System: 28x1 mm
Energy Density		Up to 1200 mJ/cm <sup>2</sup> for direct transfer from Epi Wafer
Substrates		
Donor		
Material		Quartz or sapphire wafer of temp. carrier
Dimensions		4" to 8" round or square (customization possible)
microLEDs		Size down to 5 x 5 µm <sup>2</sup> , street width down to 5 µm (CoW and CoC)
Receiver		
Material		Technical glass, backplane, temp. carrier
Dimensions		Max. 400 x 600 mm <sup>2</sup> (GEN 2.5 substrates)
Stage Systems		
Donor Stage		Options - Triple donor stage for RGB generation in one step - Single donor stage with bow compensation
Receiver Stage		Double receiver stage for parallel processing and loading/unloading/alignment
Diagnostic Systems		
Donor Diagnostics		Fiducial and alignment camera
Receiver Diagnostics		Fiducial and alignment camera Optional: Full sample scanning camera for anomaly detection
Beam Diagnostics		Power meter and beam profiler
Additional Diagnostics		On axis gap measurement system Through the lens camera
Housing		
Laser Protection Class		CLASS IV LASER RADIATION PRODUCT PER EN/IEC 60825-1: 2014
Temperature Control		Temperature stabilization ±0.3 K
Control of Particle Contamination		ISO class 5 in process chamber Optional: Advanced air cleaning system for "ISO 1 mini environment" in the process area
SW and Automatization		
SW Features		Path planning and process simulation Digital twin Fab integration according to customers infrastructure
Automatization		Fully automated process flow EFEM integration according to customer needs

Additional Information

